

Sheet 1 of 1

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)
3526.4US (97-1136.05/US)

Application Number
09/711,324

Applicant Ko et al.

Filing Date November 13, 2000

Group Art Unit 1765

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
K-cc	4,529,476	07/1985	Kawamoto et al.			
K-cc	6,018,184	01/2000	Becker			
K-cc	6,066,555	05/2000	Nulty et al.			
K-cc	6,110,831	08/2000	Cargo et al.			
K-cc	6,117,791	09/2000	Ko et al.			
K-cc	6,277,720 B1	08/2001	Doshi et al.			
K-cc	6,303,496 B1	10/2001	Yu			
K-cc	6,483,172 B1	11/2002	Cote et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
K-cc	61251138	08/1986	JP				abstract only
K-cc	0721205 A2	07/1996	EPO				
K-cc	WO 98/49719	11/1998	PCT				

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

K-cc	Wolf, S., et al., Silicon Processing for the VLSI Era, Vol. 1, Process Technology, Lattice Press, 1986, pp. 520-523.
No filing date	Williams, K., BSAC Etch Rates for Micromachining and IC Processing, U.C. Berkeley Microfabrication Lab., Berkeley Sensor & Actuator Center, http://www-bsac.eecs.berkeley.edu/lab/etchrates.html .
K-cc	Williams, K., VLSI Etchants, Chapter 1.5, Rev. 11/97, http://microlab.berkeley.edu/labmanual/chap1/1.5.html .
EXAMINER	DATE CONSIDERED
K-cc. H. E. L.	Feb 9, 2004

EXAMINER: Initial if citation considered; whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.